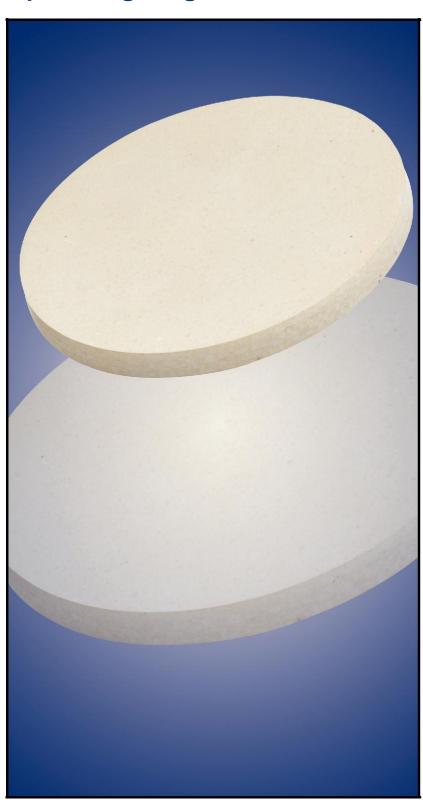
# **Strontium** Titanate SrTiO3



## **Advanced Engineering Materials**

# **Sputtering Targets**



### **Applications**

- Ferroelectric
- CMOS
- · Thin film capacitor

#### **Features**

- High purity
- · Custom Sizes Available

#### **Process**

- Manufacturing
- Cold pressed
- Sintered
- Elastomer bonded to backing plate
- Cleaning and final packaging
  Cleaned for use in vacuum
  - Protection from environmental contaminants
  - Protection during shipment

### **Options**

- 99.9% Minimum Purity
- Up to 12.0" Diameter Targets Available
- · Planar Tiles Up to 8" X 5" for Larger **Target Configurations**

## **Specifications**

### Typical Analysis - 99.9% (3N) Purity

Metallic Impurities, ppm by weight

Al	Ва	Bi	Ca	CI	Co	Cr	Fe	Hf	K
<5	<5	<5	<15	<15	<5	<5	<5	<20	<5

Mg	Mn	N	Na	Ni	Pb	S	Sb	Si	Sn
<5	<5	<50	<50	<5	<5	<5	<5	<5	<5

Theoretical Density	5.1 g/cc
Typical Density	3.66 g/cc
Sputter	RF
Max Power Density (Watts/Square Inch)	20
Appearance	White/Beige
Z Ratio	0.31
Particle Size	D50

# **Advanced Engineering Materials**

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